

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	1	"6880260".pn.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
2	BRS	L2	2	"6080260".pn.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
3	BRS	L3	2	"6680260".pn.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
4	BRS	L4	10	(rough\$4) near15 (argon) near15 (anneal\$3)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
5	BRS	L5	16	(rough\$4) near15 (ar) near15 (anneal\$3)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L6	53	(thickness) near15 (ar) near15 (anneal\$3)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
7	BRS	L7	459	(rough\$4) near15 (argon)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
8	BRS	L8	61	(polish\$3) near15 (rta or rapid near thermal near annealing)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
9	BRS	L9	20	8 and (rough\$4)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
10	BRS	L10	14	8 and (roughness)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
11	BRS	L11	2	"5856027".pn.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
12	BRS	L12	174	(chamber) near15 (anneal\$3) near15 (argon or ar)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
13	BRS	L13	58	((chamber) near15 (anneal\$3) near15 (argon or ar) near25 (temperature or pressure))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
14	BRS	L14	886	(sacrificial near3 oxidation)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
15	BRS	L15	1	(sacrificial near3 oxidation) near15 (slip)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
16	BRS	L16	1	(sacrificial near3 oxid\$5) near15 (slip)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
17	BRS	L17	71	(oxid\$5) near15 (slip) near15 (wafer)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
18	BRS	L18	23	(oxidation) near15 (slip) near15 (wafer)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
19	BRS	L19	0	(oxid\$5) near15 (slip) near15 (wafer) near15 (rough\$4)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
20	BRS	L20	0	(oxid\$5) near15 (slip) near15 (wafer) same (rough\$4)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
21	BRS	L22	2	(oxidation) near15 (slip) near15 (wafer) and (roughness)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
22	BRS	L21	21	(oxid\$5) near15 (slip) near15 (wafer) and (rough\$4)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B